

REMARKS/ARGUMENTS

Favorable reconsideration of this application as presently amended and in light of the following discussion is respectfully requested.

Claims 1-25 are presently active in this case, Claims 1, 6, 11-13 and 25 amended by way of the present amendment.

In the outstanding Official Action, the Election/Restriction Requirement was withdrawn; Claims 1-4, 6-13 and 25 were rejected under 35 U.S.C. § 102(b) as being anticipated by U.S. Patent No. 5,875,558 to Bakke et al.; Claim 5 was rejected under 35 U.S.C. § 103(a) as being unpatentable over Bakke et al.; and Claims 14-24 were allowed.

First, Applicants wish to thank the Examiner for withdrawing the previous Restriction Requirement and examining all claims on the merits. Further, Applicants wish to thank the Examiner for allowance of Claims 14-24.

In addition, Applicants wish to thank the Examiner for the September 27, 2005 personal interview at which time the outstanding issues in this case were discussed. During the interview, Applicants presented amendments and arguments substantially as indicated in this response. While no formal agreement was reached, the Examiner indicated that the amendments contained herein appear to overcome the prior art of record.

Turning now to the merits, in order to expedite issuance of a patent in this case, Applicants have amended Claims 1 and 25 to clarify the patentable distinctions of the present invention over the cited reference to Bakke et al. Specifically, Applicants have amended Claim 1 to clarify that the indication feature is configured to uniquely associate the go no-go gauge with at least one of a plasma process chamber kit part and a process to which the process chamber kit part will be exposed.

In contrast, the cited reference to Bakke et al. discloses a pipe size measuring tool for identifying the outer and inner diameter sizes of a pipe. Thus, as discussed in the September

27 personal interview, Bakke et al. does not relate the disclosed pipe size measuring tool with plasma process chamber part. That is, Bakke et al. does not disclose an identification feature configured to uniquely associate the go no-go gauge with at least one of the plasma process chamber kit part and a process to which the plasma chamber kit part will be exposed as required by Claims 1 and 25.

Thus, Claims 1 and 25 patentably define over the cited references. As Claims 2-13 depend from Claim 1, these claims also patentably define over the cited references.

Consequently, in view of the present amendment, no further issues are believed to be outstanding in the present application and the present application is believed to be in condition for formal allowance. An early and favorable action is therefore respectfully requested.

Respectfully submitted,

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